



Atty. Dkt. No. 039153-0381

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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Ramkumar SUBRAMANIAN, et al.  
Title: TWO MASK PHOTORESIST EXPOSURE  
PATTERN FOR DENSE AND ISOLATED  
REGIONS  
Appl. No.: 09/887,035  
Filing Date: 06/25/2001  
Examiner: K. Sagar  
Art Unit: 1756

RECEIVED  
SEP 03 2003  
TC 1700

**REQUEST FOR RECONSIDERATION**

Mail Stop NON-FEE AMENDMENT  
Commissioner for Patents  
PO Box 1450  
Alexandria, Virginia 22313-1450

Sir:

This communication is responsive to the Office Action dated June 5, 2003, concerning the above-referenced patent application.

**The listing of claims** begins on page 2 of this document.

**Remarks/Arguments** begin on page 9 of this document.

Please amend the application as follows:

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